

Serial No. 09/905,172

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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: David S. Mui et al.

Serial No.: 09/905,172

Filed: 07/13/2001

Title: ETCH PATTERN DEFINITION USING A CVD ORGANIC LAYER AS AN  
ANTI-REFLECTION COATING AND HARDMASK

Art Unit: 1765

Examiner: Deo, Duy Vu Nguyen

Docket No.: 004227USA02/ETCH/SILICON

VIA FACSIMILE 703-872-9311

Mail Stop Box AF

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**AMENDMENT AND RESPONSE**

Sir:

Responsive to the Office Action mailed April 13, 2004 in the above matter, Applicants submit the following remarks:

251 North Avenue West, 2<sup>nd</sup> Floor  
Westfield, NJ 07090

13164 Lazy Glen Lane  
Oak Hill, Virginia 20171

**Mayer, Fortkort & Williams, PC**  
**Attorneys At Law**

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**To:** Commissioner for Patents

**From:** David Bonham  
(703) 433-0510

**Fax:** 703-872-9311

**Total pages:** 16

**Phone:**

**Date:** 6/14/2004

**Re:** In connection with prosecution in Serial. No.  
09/905,172, please find enclosed a response to  
the final Office Action mailed April 13, 2004.

**CC:**

David Bonham

☐ **Urgent**    ☐ **For Review**    ☐ **Please Comment**    ☐ **Please Reply**    ☐ **Please Recycle**

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